[WeC2] Advanced Metrology & Inspection, Process Diagnostics & Control, and Yield Management IV	
Session Date	November 12 (Wed.), 2025
Session Time	14:10-15:40
Session Room	Room C (Grand Ballroom 3, 2F)
Session Chair	Dr. Ansoon Kim (KRISS, Korea)

[WeC2-1] [Invited] 14:10-14:40

Development of DUV & EUV Optics for Semiconductor Inspection

Hagyong Kihm (KRISS and Univ. of Science and Tech., Korea) and Jae-Hyuck Choi (KRISS, Korea)

[WeC2-2] [Invited] 14:40-15:10

Development of a High-Brightness LaB_6 Electron Source and REELS(Reflection Electron Energy Loss Spectroscopy)

Takashi Ogawa, Ha Rim Lee (KRISS, Korea), Youngkwon Haam (KRISS and Chungnam Nat'l Univ., Korea), Junhyeok Hwang, Jeong Woong Lee (KRISS, Korea), and In-Yong Park (KRISS, Univ. of Science and Tech., and Chungnam Nat'l Univ., Korea)

[WeC2-3] [Invited] 15:10-15:40

Applications of High-Speed AFM for Advanced Packaging, EUV Lithography and CMP

A.D. Giddings (Infinitesima Ltd., UK)